

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
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Examiner		Art Unit		Page 1 of 1
Lynette T. Umez-Eronini		1765		

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	B	US-6,403,491 B1	06-2002	Liu et al.	438/710
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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.